


IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

<p>In re application of:</p> <p>MARAKHTANOV et al</p> <p>Serial No.: 10/808,795</p> <p>Filed: March 24, 2004</p> <p>Title: PLASMA PROCESSING SYSTEM CONTROL</p>		<p>Group Art Unit: <del>2821</del> 2828</p> <p>Examiner: UNASSIGEND</p> <p>Docket: P1220/LMRX-P030</p> <p>Confirmation No.: 6020</p>
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**INFORMATION DISCLOSURE STATEMENT**

**US PATENT DOCUMENTS**

Examiner Initials	Cite No.	Document Number	Publication Date	Name of Patentee or Applicant	Reference to Related Case
D		US-5933314	1999-08-03	Lambson et al.	

**FOREIGN PATENT DOCUMENTS**

Examiner Initials	Cite No.	Document Number	Publication Date	Applicant	Reference to Related Case	T

**OTHER DOCUMENTS**

Examiner Initials	Cite No.		T
D	/	Kawamura et al., "Ion energy distributions in RF sheaths; review, analysis and simulation", 1999, Plasma Sources Science Technology 8, R45-R64.	
		Lieberman et al., "Principles of Plasma Discharges and Materials Processing", 1994, New York, John Wiley and Sons, Inc..	

Examiner Signature	David Vn	Date Considered	6/12/05
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